Paper Number(s): E1.3

IMPERIAL COLLEGE OF SCIENCE, TECHNOLOGY AND MEDICINE UNIVERSITY OF LONDON

DEPARTMENT OF ELECTRICAL AND ELECTRONIC ENGINEERING EXAMINATIONS 2001

EEE PART I: M.Eng., B.Eng. and ACGI

DEVICES AND FIELDS

Friday, 15 June 10:00 am

There are FIVE questions on this paper.

There are two sections. Answer THREE questions including at least ONE question from each section.

Use a separate answer book for each section.

Time allowed: 2:00 hours

CORRECTED

Examiners:

Wright, S.W., Cozens, J.R., Leaver, K.D.

and Green, T.C.

Formulae and Constants

For Silicon at 300K:

$$N_{\rm C}, N_{\rm V} = 2 x 10^{25} \, {\rm m}^{-3}$$
 $n_{\rm i} = 1.45 x 10^{16} \, {\rm m}^{-3}$ $\mu_{\rm e} = 1300 \, {\rm cm}^2 \, {\rm V}^{-1} \, {\rm sec}^{-1}$ $\mu_{\rm h} = 500 \, {\rm cm}^2 \, {\rm V}^{-1} \, {\rm sec}^{-1}$

$$n_i=1.45 \times 10^{16} \text{ m}^{-3}$$

 $\mu_h=500 \text{ cm}^2 \text{ V}^{-1} \text{ sec}^{-1}$

For Silicon Dioxide:

$$\varepsilon_{0x} = 4x \varepsilon_0$$

$$\varepsilon_0 = 8.85 \times 10^{-12} \text{ F m}^{-1}$$

$$e=1.6x10^{-19} \text{ C}$$
 $k=1.38x10^{-23} \text{ JK}^{-1}$

$$f(E) = \frac{1}{1 + \exp\left(\frac{E - E_F}{kT}\right)}$$

$$I_{D} = \frac{W C_{OX} \mu}{L} \left(V_{GS} - V_{T} - \frac{V_{DS}}{2} \right) V_{DS} \quad (V_{GS} - V_{T}) > V_{DS} > 0$$

$$C_{OX} = \frac{\varepsilon_0 \varepsilon_{OX}}{t_{OX}} \qquad n = N_C f(E) \qquad n \times p = n_i^2 \qquad \frac{D}{\mu} = \frac{kT}{e}$$

$$n = N_C f(E)$$

$$n \times p = n_i^2$$

$$\frac{D}{u} = \frac{kT}{e}$$

SECTION A

Use a separate answer book for each section

- 1. A silicon p-n junction diode has an acceptor doping density of 10^{24} m⁻³ and a donor doping density of 10^{22} m⁻³.
 - i Calculate the concentrations of electrons and holes at 300K in both the p and n type regions, far away from the junction. [4]
 - ii Sketch an energy level diagram for this diode when unbiased, labelling the Fermi level and the conduction and valence bands.
 - iii Give a labelled sketch of the distributions of minority carriers in the diode when it is (a) forward biased and (b) reverse biased, assuming that it behaves as a short diode. [4]
 - iv What is the significance of the word 'short' in the description of this diode? [2]
 - v From your diagram, deduce an expression for the reverse saturation current density of this diode, and evaluate it given that the n- and p- regions each have a length of 120μ m.
 - vi What would be the value of the reverse saturation current density if the acceptor doping density is reduced by a factor of 10^3 ?

Figure 1 shows the dependence of drain current on gate-source voltage for a particular silicon MOSFET measured using a source-drain voltage V_{DS} of 0.1V

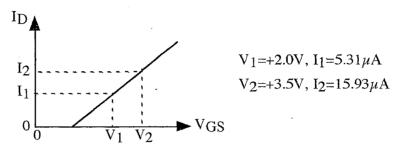


Figure 1 Drain current vs Gate-source voltage characteristic of a MOSFET

- i What type of MOSFET is this the characteristic of? [2]
- ii What is meant by the threshold voltage? [2]
- iii Calculate the values of the threshold voltage and transconductance [6] for this MOSFET.
- iv If the device dimensions have the following values, calculate the mobility of the current carriers in the MOSFET channel length=1µm, channel width=2µm, insulator thickness=50nm.
- v Why is the value of mobility lower than that which would be measured in a sample of bulk silicon? [2]
- vi What would be the dependence of I_D on V_{GS} in the saturation region of operation? [2]
- 3. i Sketch the form of the Fermi-Dirac distribution function for T=0K and T>0K, [4] showing the position of the Fermi energy, and the value of the function at that energy.
 - ii State briefly the physical meaning of the Fermi-Dirac distribution function [2]
 - iii Calculate the differences in energy at 300K between the conduction band and Fermi level for n-type and p-type silicon, doped in each case with 10²³ m³ doping atoms.
 - iv Sketch the small-signal equivalent circuit of a bipolar transistor, labelling each component in the equivalent circuit. [4]
 - v Explain briefly how the design of a bipolar transistor can be optimised to [4] increase the current gain

SECTION B

Use a separate answer book for each section

4. State Gauss' Law in electrostatics.

[4]

a) A parallel plate capacitor with plates of area A and separation d, has a block of dielectric, of relative permittivity ε , of cross-sectional area A, and thickness t (t < d), inserted between the plates.

Find the values of the electric field strength E, and the electric flux density D, in both the air and the dielectric.

[4]

Show that the capacitance of the capacitor is given by

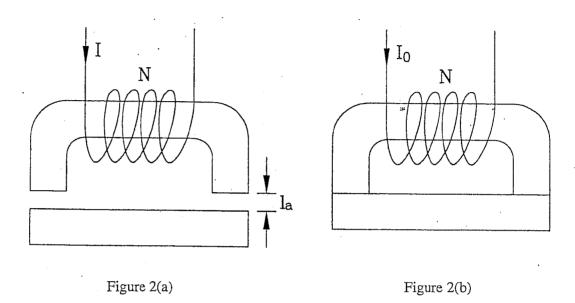
$$C = A\varepsilon\varepsilon_0 / [\varepsilon d - (\varepsilon - 1)t].$$
 [6]

b) The values of the vertical potential gradient at heights of 100 and 1000 metres above the earth's surface are 110 and 25 V/metre respectively. What is the mean electrostatic charge per cubic metre of the atmosphere between these heights? [6] $(\epsilon_0 = 8.85 \times 10^{-12} \text{ F/m})$

5. State Ampere's Law in magnetostatics.

[4]

An electromagnet is held close to a piece of iron, of mass m, which is lying freely on a wooden surface, as shown in figure 2(a).



Deduce an expression for the magnetic flux in the iron when a current of I amps flows through the coil, and also for the inductance of the coil. [4,2]

By considering the energy stored in an inductor, or otherwise, deduce an expression for the force pulling the iron piece towards the electromagnet. [4]

Given that the relevant parameters are as follows;

Total path length in iron = 1m Each air gap = 5 mm. Cross Sectional area = 25 cm² Number of turns = 100 Mass of iron piece = 2 kg Relative permeability of iron = 10^4 p = $4\pi 10^{-7}$ F/m g = 9.81 m/s²

calculate a value for the minimum current, I_0 , required to lift the iron from the surface. [4]

If the iron is brought into contact with the electromagnet, as shown in figure 2(b), and the current I_0 is maintained, what is the minimum force required to separate the iron from the magnet?

(iii)

(1)
$$n \text{ side } n = N_D = 10^{22} \text{ m}^{-3}$$

$$P_n = N_c^2 = \frac{(1.45 \times 10^{16})^2}{10^{22}} = 2.025 \times 10^{10} \text{ m}^{-3}$$

$$N_D = \frac{10^{22}}{10^{22}} = \frac$$

Pside
$$P_P = N_A = 10^{24} \text{ m}^{-3}$$

$$N_P = N_a^2 = \frac{(1.45 \times 10^{16})^2}{10^{24}} = 2.025 \times 10^8 \text{ m}^{-3}$$

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Answers E1.3

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(1V) A short diode - no recombin recombination of minority carriers can be reglected

Minority contier distributions in (iii) above are then linear

 $(V) \quad J_s = e \left(\frac{D_e n_p}{L_p} + \frac{D_h p_n}{L_n} \right) \quad [2]$

Die so Js = kT (Me Mp + Mn Pn)
Lp Ln)

 $= 1.38 \times 10^{-23} \times 300 \left(0.13 \times 2.025 \times 10^{8} + \frac{0.05 \times 2.025 \times 10^{10}}{120 \times 10^{-6}} \right)$

= $4.14 \times 10^{-21} \left(2.19 \times 10^{11} + 8.44 \times 10^{12} \right)$

 $= 3.58 \times 10^{-8} \text{ Am}^{-2} \qquad [3]$

(VI) If NA and hence pp reduced by 103

Np becomes 2.025 × 10 m-3

so thus first torm in above increased by ×103
[2]

Se Jsc = 4.14 ×10-21 (2.19×1014 +8.44×1012)

= 9.42×10-7 Am-2

(20) E1.3

This is an n-channel, enhancement mode MOSFET [2]

(ii) Threshold voltage: the gate-source voltage

Which is needed to course formation of a Conducting channel between source e drain [2]

or The gate-source voltage which inverts the surface of the silicon

(11) $I_D = K V_{GS} - V_T$ if $V_{DS} \ll (V_{GS} - V_T)$

So $\frac{I_{D_2}}{I_{D_1}} = \frac{V_{GS_2} - V_{\tau}}{V_{GS_1} - V_{\tau}}$ so $\frac{15.93}{5.31} = 3 = \frac{3.5 - V_{\tau}}{2 - V_{\tau}}$

so $3(2-V_{\tau})=(3.5-V_{\tau})$

 $V_T = 1.25v$

 $g_{m} = dI$ = $I_{2}-I_{1}$ = 10.62 = 7.08, A/V₀/b dV_{GS} = $V_{2}-V_{1}$ = 1.5

[3]

Where
$$Cox = \frac{660x}{tox} = \frac{4x8.85x10^{-12}}{50x10^{-9}} = 7.08x10^{-4} Fm^{-2}$$

$$50 \text{ M} = \frac{9 \text{ m}}{2 \cdot 08 \times 10^{-6}}$$

$$\frac{2 \times 7.08 \times 10^{-6}}{2 \times 7.08 \times 10^{-4} \times 0.1}$$

$$= 0.05 \text{ m}^2/\text{Vsec}$$

[4]

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(11) F-D function - the value at energy E is the probability of a state at energy E being [2] occupied by an election.

(iii)
$$n$$
-type $n = N_c f(E_c) \simeq N_c e^{-(E_c - E_f)}$
so $E = k + ln N_e$
and $n = N_D = 10^{23} \text{ ps} \text{ m}^{-3}$

So $E_{c}-E_{F}=kT \ln \frac{1}{2}\left(\frac{2\times10^{25}}{10^{23}}\right)=0.138eV$

p-type
$$n = Nc exp - \left(\frac{Ec - EF}{ET}\right)$$

and $\Omega = Ni^2 = Ni^2 = 246 \left(\frac{1.45 \times 10^{16}}{10^{23}}\right)^2$
= 2.025×10⁹ m⁻³ [2]

 $so E_c - E_F = \frac{RT}{e} lw \left(\frac{2 \times 10^{25}}{(2.035 \times 10^9)} \right) = 0.957 eV \left[\frac{2}{2} \right]$

Q3 (iv)

B

gmvbe

Fre

G

Fre

[4]

- (V) To improve gain of bipolar transister
 - (a) Make base nation reduces IB by reducing minority carrier recombination

increases Ic because steeper [4] concentration gradient in base

(b) Heavily dope emitter - reduce carrier injection from beeze to emitter,

Section B.

from youngetry lines of electoric flux density are normal to

In all regions D=0 (chaqe/unit area) regions 123 E=D=0

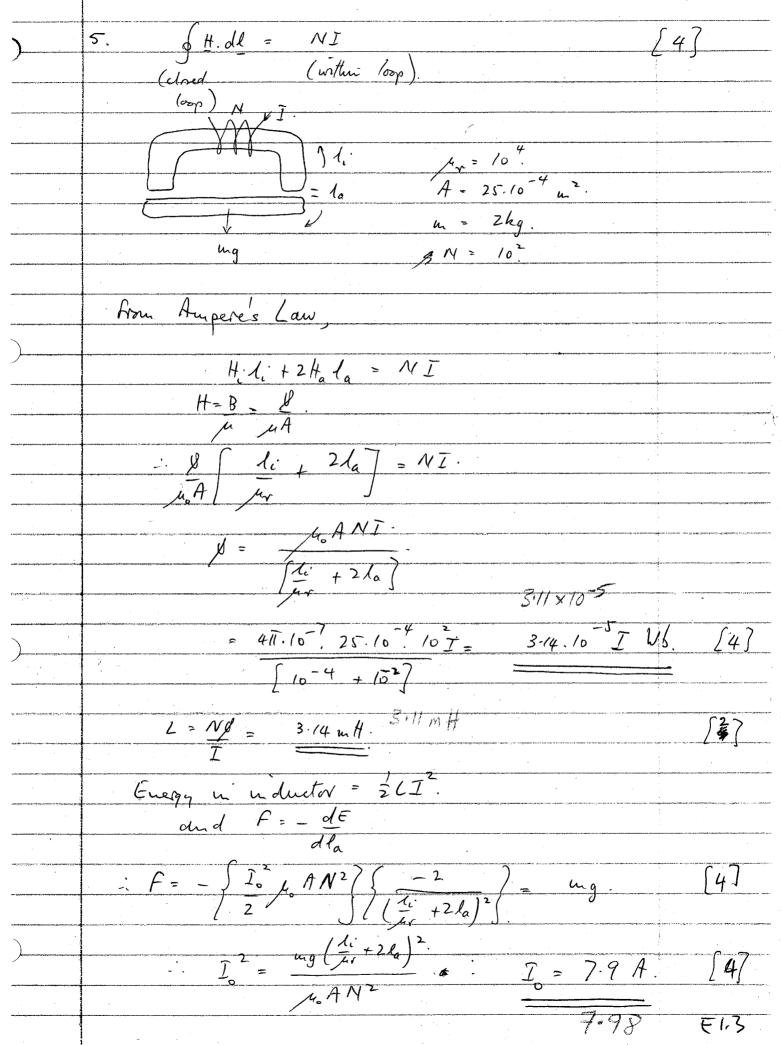
In all regins, $E = -\frac{dV}{dn}$ \therefore in $D = V_2 - V_1 - \left(\frac{D}{2}\right) \ell_1$

 $v_3 - v_2 = \left(\frac{O}{\xi_0 \xi}\right) t$

 $\frac{1}{4} \frac{3}{4} \frac{V_4 - V_3}{4} = \left(\frac{5}{2}\right) \frac{1}{2}$

Volt drop across whole capacitor - V4-V, = 0 / 1,+13 + 67

Charge on plates = OA = P,



Page 10/10 I 4. AN = 7.9. 41.10.25.10.4 10 F = 1.96.10 N 527 2.00 × 105 N